

In The Claims

1. (Currently Amended) A process for the production of a heat-treatable low emissivity coated glass that comprises the steps of:
 - a) depositing an underlayer onto a glass substrate by a pyrolytic deposition process, and
 - b) subsequently depositing a reflective metal layer by a vacuum deposition method, directly on the underlayer,
wherein the under layer comprises a silicon oxide.
2. (Cancelled)
3. (Canceled)
4. (Previously Presented) A process according to claim 1 wherein the underlayer comprises a silicon oxide containing carbon.
5. (Previously Presented) A process according to claim 1 wherein the pyrolytic deposition of the underlayer comprises contacting the glass substrate with a fluid mixture containing a silicon source, an oxygen source and a carbon source under conditions such that a silicon oxide layer, preferably containing carbon, is deposited.
6. (Previously Presented) A process according to claim 5 wherein the fluid mixture is a vapor mixture.
7. (Previously Presented) A process according to claim 1 wherein the underlayer comprises silicon oxide containing nitrogen.

8. (Previously Presented) A process according to claim 1 wherein the underlayer is deposited on the glass substrate when the glass substrate is at a temperature in the range 450°C to 800°C.

9. (Original) A process according to claim 8 wherein the underlayer is deposited on the glass substrate when the glass substrate is at a temperature in the range 600°C to 780°C.

10. (Previously Presented) A process according to claim 1 wherein the underlayer is deposited on to a glass ribbon during the float glass production process at substantially atmospheric pressure.

11. (Original) A process according to claim 10 wherein the glass ribbon is cut into sheets after deposition of the underlayer.

12. (Previously Presented) A process according to claim 1 wherein the reflective metal layer comprises silver or aluminum.

13. (Previously Presented) A process according to claim 1 wherein an anti-reflection layer is deposited by a vacuum deposition process on to the coated glass after deposition of the reflective metal layer.

14. (Original) A process according to claim 13 wherein the anti-reflection layer comprises a metal oxide.

15. (Original) A process according to claim 14 wherein the anti-reflection layer comprises zinc oxide or tin oxide.

16. (Previously Presented) A process according to claim 13 wherein a second reflective metal layer and a second anti-reflection layer are sequentially deposited by a vacuum deposition process after deposition of the first anti-reflection layer.

17. (Previously Presented) A process according to claim 1 additionally comprising a heat treatment step wherein the heat-treatable low emissivity coated glass is subjected to a temperature in the range 400 to 750°C in an oxidizing atmosphere.

18. (Original) A process according to claim 17 wherein the heat treatment step is directed to the production of bent and/or toughened coated glass.

19. (Previously Presented) A process according to claim 17 wherein the visible transmission of the coated glass is increased by the heat-treatment step.

20. (Previously Presented) A coated glass produced by a process according to claim 1.

21. (Currently Amended) A heat-treatable low emissivity coated glass comprising a glass substrate having a multilayer coating on one surface, said multilayer coating comprising a pyrolytically deposited underlayer which comprises a silicon oxide and is deposited directly on the glass, a vacuum deposited reflective metal layer that is deposited directly on the underlayer, and a vacuum deposited anti-reflection layer.

22. (Original) A coated glass according to claim 21 wherein the underlayer comprises a silicon oxide.

23. (Original) A coated glass according to claim 22 wherein the underlayer comprises a silicon oxide containing carbon.

24. (Previously Presented) A coated glass according to claim 21 wherein the underlayer has a refractive index in the range 1.5 to 3.
25. (Previously Presented) A coated glass according to claim 21 wherein the underlayer has a thickness in the range 30 to 100 nm.
26. (Previously Presented) A coated glass according to claim 21 wherein the reflective metal layer has a thickness in the range 5 to 30 nm.
27. (Original) A coated glass according to claim 26 wherein the reflective metal layer has a thickness in the range 7 to 18 nm.
28. (Previously Presented) A coated glass according to claim 21 wherein the anti-reflection layer has a thickness in the range 30 nm to 90 nm.
29. (Previously Presented) A coated glass according to claim 21 wherein the coated glass has a normal emissivity of below 0.2.
30. (Previously Presented) A coated glass according to claim 21 wherein the coated glass has a normal emissivity of below 0.1.
31. (Previously Presented) A coated glass according to claim 21 wherein the coated glass has been heat treated by heating it to a temperature in the range 400 to 700°C in an oxidizing atmosphere.
32. (Original) A coated glass according to claim 31 wherein the coated glass has a normal emissivity of below 0.2 after the heat treatment step.

33. (Original) A coated glass according to claim 32 wherein the coated glass has a normal emissivity of below 0.1 after the heat treatment step.

34. (Current Amended) A heat-treatable low emissivity coated glass comprising a glass substrate having a multilayer coating on one surface, said multilayer coating comprising an oxygen scavenging underlayer comprising a silicon oxide, a vacuum deposited reflective metal layer that is deposited directly on the underlayer and a vacuum deposited anti-reflection layer.

35. (Original) A multiple glazing unit comprising a first glazing pane of a coated glass according to claim 34 and a second glazing pane.

36. (Original) Laminated glass comprising a first glazing pane of a coated glass according to claim 34, an interlayer and a second glazing pane.

37. (Canceled)